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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
09/875,197	06/07/2001	Joon-Young Yang	8733.132.20 8761			
30827 75	90 06/28/2005	EXAMINER				
MCKENNA LONG & ALDRIDGE LLP 1900 K STREET, NW			RAO, SHR	RAO, SHRINIVAS H		
WASHINGTO			ART UNIT	PAPER NUMBER		
			2814			
			DATE MAILED: 06/28/2009	5		

Please find below and/or attached an Office communication concerning this application or proceeding.

## Advisory Action Refore the Filing of an Appeal Brief

Application No.	Applicant(s)	_
09/875,197	YANG, JOON-YOUNG	
Examiner	Art Unit	_
Steven H. Rao	2814	

Before the Filing of an Appeal Brief	Examiner	Art Unit						
	Steven H. Rao	2814						
The MAILING DATE of this communication appears on the cover sheet with the correspondence address								
THE REPLY FILED 29 March 2005 FAILS TO PLACE THIS AF	PLICATION IN CONDITION FOR	ALLOWANCE.						
1. The reply was filed after a final rejection, but prior to or or this application, applicant must timely file one of the follow places the application in condition for allowance; (2) a Not a Request for Continued Examination (RCE) in compliant time periods:	wing replies: (1) an amendment, aff otice of Appeal (with appeal fee) in o	idavit, or other evider compliance with 37 C	nce, which FR 41.31; or (3)					
a) The period for reply expires 3 months from the mailing date	of the final rejection.							
The period for reply expires on: (1) the mailing date of this Advisory Action, or (2) the date set forth in the final rejection, whichever is later. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of the final rejection.								
Examiner Note: If box 1 is checked, check either box (a) or TWO MONTHS OF THE FINAL REJECTION. See MPEP 7	06.07(f).							
Extensions of time may be obtained under 37 CFR 1.136(a). The date have been filed is the date for purposes of determining the period of ex under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the set forth in (b) above, if checked. Any reply received by the Office later may reduce any earned patent term adjustment. See 37 CFR 1.704(b) NOTICE OF APPEAL	tension and the corresponding amount shortened statutory period for reply orig r than three months after the mailing da	of the fee. The appropri	iate extension fee ce action; or (2) as					
2. The Notice of Appeal was filed on A brief in compliance with 37 CFR 41.37 must be filed within two months of the date of filing the Notice of Appeal (37 CFR 41.37(a)), or any extension thereof (37 CFR 41.37(e)), to avoid dismissal of the appeal. Since a Notice of Appeal has been filed, any reply must be filed within the time period set forth in 37 CFR 41.37(a).  AMENDMENTS								
<ul> <li>The proposed amendment(s) filed after a final rejection, but prior to the date of filing a brief, will <u>not</u> be entered because</li> <li>(a) They raise new issues that would require further consideration and/or search (see NOTE below);</li> <li>(b) They raise the issue of new matter (see NOTE below);</li> </ul>								
(c) They are not deemed to place the application in being appeal; and/or	tter form for appeal by materially re	•	the issues for					
(d) They present additional claims without canceling a NOTE: (See 37 CFR 1.116 and 41.33(a)).		ected claims.	•					
4. The amendments are not in compliance with 37 CFR 1.1121. See attached Notice of Non-Compliant Amendment (PTOL-324).								
5. Applicant's reply has overcome the following rejection(s):								
Newly proposed or amended claim(s) would be all non-allowable claim(s):	·	•	ū					
7. Tor purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is pro The status of the claim(s) is (or will be) as follows:	□ will not be entered, or b) □ wi vided below or appended.	ll be entered and an e	explanation of					
Claim(s) allówed: Claim(s) objected to:								
Claim(s) rejected:								
Claim(s) withdrawn from consideration:  AFFIDAVIT OR OTHER EVIDENCE								
<ol> <li>The affidavit or other evidence filed after a final action, bu because applicant failed to provide a showing of good an was not earlier presented. See 37 CFR 1.116(e).</li> </ol>	at before or on the date of filing a North d sufficient reasons why the affidat	otice of Appeal will <u>no</u> vit or other evidence is	ot be entered s necessary and					
9.  The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to a showing a good and sufficient reasons why it is necessar	overcome <u>all</u> rejections under apper y and was not earlier presented. S	al and/or appellant fai ee 37 CFR 41.33(d)(	ls to provide a 1).					
10. ☐ The affidavit or other evidence is entered. An explanatio REQUEST FOR RECONSIDERATION/OTHER	n of the status of the claims after e	ntry is below or attach	ned.					
<ol> <li>The request for reconsideration has been considered bu see below.</li> </ol>	it does NOT place the application in	n condition for allowa	nce because:					
12. Note the attached Information Disclosure Statement(s).	(PTO/SB/08 or PTO-1449) Paper N	lo(s)						
13.  Other:	·							
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		,						

Applicants' analysis of the Final rejection is based on erroneous inerpretation of the finalreejction. It is noted that the Final rejection stated (in reliveant part), "forming an impurity region by heavily implanting impurity ions to said excited region in a

heavy dosage while the excited region remains in an excited state, (Fig. 1 C implanting P+ ions Yamaguchi col. 9 lines 14 and figs. I,etc. describe heavily implanting ions,). (It is noted that Yamaguchi discloses the use of active layer as a mask and implanting prior to the formation of the gate. However it would be an obvious altering of the sequence of steps to implant the H after gate formation. Further as Applicants' claims use the terminology " comprising" the claim includes steps in any sequence)

Yamaguchi does not specifically disclose the limitation, 'land has a temperature high enough to self-activate the impurity ions and whereby impurity ions become self-activated". However, Aomori, a patent from the same filed of endeavor, describes in col.3 lines 13 to 25 ion shower doping method wherein heavy doping/implantation of Hydrogen ions the impurity ions are self-activated in the polycrystalline thin film to fabricate TFTS at low temperature thereby allowing the use of low temperature melting materials to be used and to control the precise amount of Hydrogen to be implanted is attained thereby a TFT with higher reliability is obtained. And in col. 1 1 lines 53-55. Further it is noted that it is well known in the art that one form of shower dopign is implantation (e.g. see USP No.. 4,851,363) Therefore Aomori does not teach away and can be properly combined with Yamaguchi. The sequential implatation/doping of ions is taught by applied Yamaguchi and this teaching need not be repated also by Aomori. Therefore allof Applicants' agumetns are not persuaisve.

SX 6/24/05

LONG HAM
PRIMARY EXAMINER